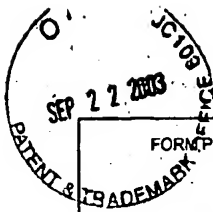


FORM PTO-1449 U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE	ATTY. DOCKET NO. ASMEX.284C1	APPLICATION NO. 10/826,212
INFORMATION DISCLOSURE STATEMENT BY APPLICANT		
APPLICANT Pomareda, et al.		
FILING DATE July 24, 2003		GROUP Unknown 2823
(USE SEVERAL SHEETS IF NECESSARY)		

U.S. PATENT DOCUMENTS							
EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE (IF APPROPRIATE)
Lee	1	2,394,930	2/12/46	McRae			
	2	3,895,127	7/15/75	Comizzoli			
	3	4,056,642	11/1/77	Saxena et al.			
	4	4,292,343	9/29/81	Plaettner et al.			
	5	4,343,830	8/10/82	Sarma et al.			
	6	4,436,761	3/13/84	Hayashi et al.			
	7	4,544,571	10/1/85	Miller			
	8	4,645,683	2/24/87	Gourrier et al.			
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	11	5,281,546	01/25/94	Possin et al.			
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	19	6,107,192	08/22/00	Subrahmanyam et al.			
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FOREIGN PATENT DOCUMENTS								
EXAMINER INITIAL		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
							YES	NO
<i>Lu</i>	21	JP 60 254621 A	16.12.85	Patent Abstracts of Japan				
<i>Lu</i>	22	JP 2000 160342 A	13.10.00	Patent Abstracts of Japan				
<i>Ne</i>	23	0 617 461 A2	03/16/94	EPO				

EXAMINER Brian May Lee	DATE CONSIDERED 5/27/2004
*EXAMINER: INITIAL IF CITATION CONSIDERED, WHETHER OR NOT CITATION IS IN CONFORMANCE WITH MPEP 609; DRAW LINE THROUGH CITATION IF NOT IN CONFORMANCE AND NOT CONSIDERED, INCLUDE COPY OF THIS FORM WITH NEXT COMMUNICATION TO APPLICANT.	



FORM PTO-1449 U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE	ATTY. DOCKET NO. ASMEX 284C1	APPLICATION NO. 10/626,212
INFORMATION DISCLOSURE STATEMENT BY APPLICANT (USE SEVERAL SHEETS IF NECESSARY)	APPLICANT Pomareda, et al.	
	FILING DATE July 24, 2003	GROUP Unknown 2823

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<i>Re</i>	24 Kim, H. and R. Reif, <i>Thin Solid Films</i> , Vol. 289:192-198 (1996), "In-situ low-temperature (600°C) wafer surface cleaning by electron cyclotron resonance hydrogen plasma"
<i>Lu</i>	25 Ramm J. and E. Beck, <i>Thin Solid Films</i> , Vol. 246:158-163 (1994), "Low temperature epitaxial growth by molecular beam epitaxy on hydrogen-plasma-cleaned silicon wafers."

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EXAMINER <i>Kevin Ming Lee</i>	DATE CONSIDERED <i>5/27/2004</i>
*EXAMINER: INITIAL IF CITATION CONSIDERED. WHETHER OR NOT CITATION IS IN CONFORMANCE WITH MPEP 609, DRAW LINE THROUGH CITATION IF NOT IN CONFORMANCE AND NOT CONSIDERED. INCLUDE COPY OF THIS FORM WITH NEXT COMMUNICATION TO APPLICANT.	